# Oxygen-doped Ta<sub>3</sub>N<sub>5</sub> modified with a Ru(II) binuclear complex having the ability to reduce CO<sub>2</sub> under a wide range of visible light

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**Abstract:** A hybrid photocatalyst constructed with  $Ta_3N_5$  and a binuclear ruthenium(II) complex had the ability to reduce  $CO_2$  into HCOOH with very high selectivity (>99%) under a wide range of visible light ( $\lambda$  > 500 nm). In particular,  $Ta_3N_5/SiO_2$  prepared from  $Ta_2O_5$ , which was loaded on SiO<sub>2</sub> by a sol-gel method, showed 4–6 times higher activity than the bulk type  $Ta_3N_5$ . UV-vis diffuse reflectance spectra showed that the background absorption of the  $Ta_3N_5/SiO_2$  spectrum, which is attributed to tantalum reduced species, was reduced, compared to the bulk  $Ta_3N_5$ . The decrease of the defect density contributed to the suppression of the charge recombination, resulting in higher activity of  $Ta_3N_5/SiO_2$ .

Keywords: CO<sub>2</sub> fixation, (Oxy)nitride, Metal complex.

## 1. Introduction

There are many reports on tantalum nitride  $(Ta_3N_5)$  for photocatalytic or photoelectrochemical water splitting, because  $Ta_3N_5$  has wide range of visible light absorption property and suitable band edge position for water splitting.<sup>1</sup> However, there is no report on application of  $Ta_3N_5$  for photocatalytic CO<sub>2</sub> reduction. In order to enhance the photocatalytic activity, it is well known that in the synthesis of Ta-based oxynitrides, suppressing the Ta reduced species is important, which acts as a recombination center of charge carrier.<sup>2</sup> Herein we report that  $Ta_3N_5$  can reduce CO<sub>2</sub> to HCOOH when combined with a Ru(II) binuclear complex (**RuRu'**) under the irradiation of visible light ( $\lambda > 500$  nm). In particular, we focused on interfacial interaction between anion (in particular oxygen) and  $Ta_3N_5$  by using composite of  $Ta_2O_5$  loaded on SiO<sub>2</sub> as a precursor, which is considered to have interaction between oxygen within SiO<sub>2</sub> and Ta.<sup>3,4</sup> This method is based our previous report, in which ZrO<sub>2</sub>-modified TaON showed higher activity by utilizing interaction between the two components, resulting in suppression of reduced Ta species.<sup>5</sup> In this work, we successfully suppressed the production of the undesirable reduced Ta species in  $Ta_3N_5$ , thereby improving photocatalytic CO<sub>2</sub> reduction activity.

#### 2. Experimental (or Theoretical)

In this work,  $Ta_3N_5$ -loaded SiO<sub>2</sub> ( $Ta_3N_5$ /SiO<sub>2</sub>) was synthesized by thermal ammonolysis of  $Ta_2O_5$ /SiO<sub>2</sub>, which was in prior prepared by a sol-gel method, with dry annmonia.<sup>3,4</sup> Powders of bulk  $Ta_3N_5$  and nanoparticulate  $Ta_3N_5$  were also synthesized as references according to the methods reported previously.<sup>5</sup> These reference samples are represented hereafter as bulk- $Ta_3N_5$  and nano- $Ta_3N_5$ , respectively. Each nitride sample was characterized by X-ray diffraction (XRD), UV-visible diffuse reflectance spectra (DRS), X-ray photoelectron spectroscopy (XPS), scanning electron microscope (SEM) and transmission electron microscope (TEM). Prior to CO<sub>2</sub> reduction, the as-prepared  $Ta_3N_5$  samples were modified with both Ag nanoparticles and a **RuRu'**, which work as an electron-transfer promoter and a photocatalytic unit having a high ability to reduce CO<sub>2</sub>, respectively.

## 3. Results and discussion

XRD and DRS showed that the single phase  $Ta_3N_5$  was produced in each nitrided sample. To investigate the possible incorporation of oxygen into the lattice of  $Ta_3N_5$ , XPS measurements were

conducted. The Ta  $4f_{7/2}$  peak positions in Bulk-Ta<sub>3</sub>N<sub>5</sub> and Nano-Ta<sub>3</sub>N<sub>5</sub> (24.6 eV) were in good agreement with previous reports.<sup>6</sup> On the other hand, the peak position in Ta<sub>3</sub>N<sub>5</sub>/SiO<sub>2</sub> (25.0 eV) is located between the Ta<sub>3</sub>N<sub>5</sub> references (24.6 eV) and TaON (25.2 eV), which is intermediate product between Ta<sub>2</sub>O<sub>5</sub> and Ta<sub>3</sub>N<sub>5</sub>. This result clearly indicates that there is much more contribution of Ta–O bondings in Ta<sub>3</sub>N<sub>5</sub>/SiO<sub>2</sub> than those in pure Ta<sub>3</sub>N<sub>5</sub> samples.

The incorporation of oxygen into  $Ta_3N_5$  was found to alter the optical absorption profile of  $Ta_3N_5$ . Figure 1 shows the DRS of each  $Ta_3N_5$  sample. The absorption edge position of  $Ta_3N_5$  is consistent with the previous report<sup>6</sup>. However, the absorption edge of  $Ta_3N_5/SiO_2$  is located at ca. 580 nm, 20 nm blue-shifted compared to other  $Ta_3N_5$  samples. This is primarily attributed to the higher oxygen concentration in



**Figure 1** UV-visible diffuse reflectance spectra for Ta<sub>3</sub>N<sub>5</sub> samples

 $Ta_3N_5/SiO_2$  than the others, as indicated by XPS. The absorption at wavelength regions longer than 600 nm, attributed to reduced tantalum species,<sup>2</sup> is different from each other. The fact that  $Ta_3N_5/SiO_2$  has the weakest absorption in the longer wavelength region compared to Bulk- $Ta_3N_5$  and Nano- $Ta_3N_5$  indicates that formation of anionic defects during nitridation is most effectively suppressed in  $Ta_3N_5/SiO_2$ .

Using as-prepared  $Ta_3N_5$  and **RuRu'**, CO<sub>2</sub> reduction was conducted. All  $Ta_3N_5$  samples were capable of reducing CO<sub>2</sub> into HCOOH under visible light with high selectivity (~99%) (Table 1). In particular,  $Ta_3N_5/SiO_2$  showed 4–6 times higher activity than the other  $Ta_3N_5$  samples. As mentioned above,  $Ta_3N_5/SiO_2$  has the weakest absorption in the longer wavelength region than band gap transition, which is derived from reduced tantalum species (i.e., anionic defects). The lower density of defects in  $Ta_3N_5/SiO_2$  is most likely to contribute to suppression of electron–hole recombination, leading to higher activity. In addition, an increase in the driving force for reduction/oxidation processes that resulted from the blue-shift of the absorption edge (see Figure 1) might be responsible to higher activity as well.

Sample	Amount of product / nmol (TON)			Selectivity <sub>HCOOH</sub> / %
	НСООН	СО	$H_2$	
Bulk-Ta <sub>3</sub> N <sub>5</sub>	738 (41)	N.D.	7	99
Nano-Ta <sub>3</sub> N <sub>5</sub>	1080 (60)	N.D.	13	99
Ta <sub>3</sub> N <sub>5</sub> /SiO <sub>2</sub>	4320 (240)	N.D.	7	>99

Table 1. Results of CO<sub>2</sub> reduction by RuRu'/Ag (1.5 wt%)/Ta<sub>3</sub>N<sub>5</sub><sup>a</sup>

<sup>a</sup> Reaction conditions: photocatalyst, 4.0 mg (Ag 1.5 wt%); solution, a mixture of MeCN and TEOA (4:1 v/v) 4.0 mL; light source, 400 W high pressure Hg lamp (SEN) with a K<sub>2</sub>CrO<sub>4</sub> solution filter. Reaction time: 15 h. **RuRu'** loaded was 4.5  $\mu$ mol g<sup>-1</sup>.

#### 4. Conclusions

In this work, we could apply  $Ta_3N_5$  to visible-light CO<sub>2</sub> reduction with the aid of **RuRu'**. When using  $Ta_2O_5/SiO_2$  as a precursor oxide, we could suppress the production of anion defects of  $Ta_3N_5/SiO_2$ during the nitriding reaction, resulting in higher activity of  $Ta_3N_5/SiO_2$ . It is also suggested that appropriate amount of oxygen doping into  $Ta_3N_5$  is effective for enhancing photocatalytic activity.

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